

ABSTRACT

A method for reducing the contamination of at least one optical component (2, 3) contained in the beam guidance space (6) and held by a frame (4, 5) defining the beam guidance space and a corresponding optical beam guidance system. The surfaces of the frame bordering on the beam guidance space are at least partially coated with a degassing barrier layer (7) that preferably does not increase reflectivity. The method and system have use, for example, in lithography irradiation systems working with UV light.